THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: CHIH YUAN HUAN, ET AL.	
Serial No: 10/731,150) Attorney Docket No.: MIC920041
Filed: December 10, 2003	<i>)</i>)
Title: CLEANING METHOD USING OZONE DI PROCESS	,))

SUBMISSION OF REVOCATION OF POWER OF ATTORNEY AND GRANT OF POWER OF ATTORNEY

Assistant Commissioner of Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Applicants hereby submit the attached Revocation of Power of Attorney and Grant of Power of Attorney in the above-identified application. Should there be any questions with respect to this submission a representative of the Patent Office is requested to contact the undersigned.

Respectfully submitted,

CHIH YUAN HUAN, ET AL.

Date: January 18, 2005

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Customer No. 28970

PATENT Customer No. 28970

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Patent Application and Patent Numbers:

See attached "Schedule A"

REVOCATION OF POWER OF ATTORNEY AND GRANT OF NEW POWER OF ATTORNEY

The undersigned, a representative authorized to sign on behalf of the assignee owning all of the interest in the listed and pending patent applications and issued patents on the attached sheet (Schedule A), hereby revokes all previous powers of attorney or authorization of agent granted in these patents before the date of execution hereof and appoints all the attorneys associated with Customer Number 28970.

Correspondence in this matter should be directed to:

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Date: January 10, 2005

MACRONIX INTERNATIONAL CO., LTD.

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Name: ___

Title: Dire cotor

IP & Legal Office

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	7 C	SCHEDULE A		
SERIAL NUMBER	FILING DATE		PATENT NUMBER	ISSUE DATE
		Ono Interpoly Dielectric Flor Flash		
		Memory Cells and Method for		
		Fabricating The Same Using a		
		Single Wafer Low Temperature		
10/237,668	9/10/2002	Deposition Process	6,777,764	8/17/2004
		Method for Removing Fences		
	•	Without Reduction of Ono Film		
10/230,328	8/29/2002	Thickness	6,677,255	1/13/2004
10/200,020	0,20,2002	Programming A Flash Memory		
10/230,666	8/29/2002	Cell	6,760,257	7/6/2004
10/200,000	0.20,200			
		Apparatus and Method for		
10/426,833	5/1/2003	Inhibiting Dummy Cell Over Erase	6,787,860	9/7/2004
10/420,000	0/1/2000	Transland Burning Con Cver Erace	0,707,000	0,7,200.
		Protection Layer to Prevent Under-		
10/076 620	2/19/2002	Layer Damage During Deposition	6,573,177	6/3/2003
10/076,629	2/19/2002	Sensing Method for EEPROM	0,575,177	0/3/2003
10/151 150	5/21/2002	Refresh Scheme	6,639,839	10/28/2003
10/151,150	5/2 1/2002	Semiconductor Device with	0,039,039	10/20/2003
		Minimal Short-Channel Effects and		
40/404 000	2/24/2002		C EEE OAA	4/20/2002
10/101,930	3/21/2002	Low Bit-Line Resistance	6,555,844	4/29/2003
10/10/1 000	0/04/0000	Sonos Component Having High	C 400 277	12/24/2002
10/101,922	3/21/2002	Dielectric Property	6,498,377	12/24/2002
		Method for Forming An Oxide	0.554.070	4/00/0000
10/101,931	3/21/2002	Layer on a Nitride Layer	6,551,879	4/22/2003
101100 010	7 10 10 00 0	Structure for Preventing Salicide	0.077.400	4/40/0004
10/186,619	7/2/2002	Bridging and Method Thereof	6,677,199	1/13/2004
		Method of Preventing Tungsten	0.700.004	0.00.0004
10/132,286	4/26/2002	Plugs From Corrosion	6,703,301	3/9/2004
		Method for Forming A Phase		
10/197,896	7/19/2002	Change Memory	6,759,267	7/6/2004
		Memory Device and Operation		
10/214,770	8/9/2002	Thereof	6,788,602	9/7/2004
	-8-	Method for Forming A Phase		
10/847,277	5/17/2004	Change Memory	N/A	NA
		Neural Network for Determining		
10/176,065	6/21/2002	the Endpoint in a Process	N/A	NA
		Photoresist Pump Dispense		
10/387,489	3/14/2003	Detection System	N/A	NA
		Cleaning Systems With Monitaring	•	
	5/16/2003	Functions	N/A	NA
10/600,700	6/23/2003	Peer Version Control System	N/A	NA
10/667,447	9/23/2003	Batch Order Change System	N/A	NA
		Elimination of the Fast-Erase		
10/733,230	12/12/2003	Pheonomena in Flash Memory	N/A	NA
		Cleaning Method Using Ozone DI		
10/731,150	12/10/2003	Process	N/A	NA
		Endpoint Detection in		
		Manufacturing Semi-Conductor		
İ		Manufacturing Denni-Conductor		
		Cleaning Method Using Ozone DI Process Endpoint Detection in		

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SERIAL NUMBER FILING DATE		PATENT NUMBER	ISSUE DATE	
		Program/Erase Method for P-		
		Channel Charge Trapping Memory		
10/857,866	6/2/2004	Device	N/A	NA
			_	
		Method for Reducing Dimensions		
10/465,852	6/20/2003	Between Patterns on a Hardmask	N/A	NA
•		Mathad for Raduaina Dimonsions		
10/700 040	40/40/2002	Method for Reducing Dimensions Between Patterns on a Photoresist	NI/A	NA
10/739,049	12/19/2003	Structure for Preventing Salicide	IN/A	INA
10/672 250	9/30/2003	Bridging and Method Thereof	N/A	NA
10/673,359	9/30/2003	Non-Volatile Memory Cell and	14/7	147.
10/873,142	1/14/2004	Operating Method	N/A	NA
10/073,142	171472004	Memory Device With Built-In Error-		
10/237,082	6/2/2003	Correction Capabilities	N/A	NA
10/207,002	0.2.200	Memory Device With Built-In Error-		
10/449,590	6/2/2003	Correction Capabilities	N/A	NA
		Semi-Conductor Device With		
		Minimal Short-Channel Effects and		
10/361,681	2/11/2003	Low Bit-Line Resistance	N/A	NA
		Method of Forming a Polysilicon		
		Layer Compressing		
10/715,558	11/19/2003	Microcrystalline Grains	N/A	NA
10/414,048	4/16/2003	ONO Dielectric for Memory Cells	N/A	NA
		A 11 1 61 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1		
		Method of Integrating The		
	4/40/0000	Fabrication Process for Integrated	NI/A	NA
10/418,121	4/18/2003	Circuits and Mem Devices	N/A	INA
40/007 407	2/14/2002	Method for Controlling a Butterfly Valve	N/A	NA
10/387,487 10/653,892	3/14/2003 9/4/2003	A Non-Volatile Flash Memory	N/A	NA
10/000,092	9/4/2003	Fabrication Method of Sub-	13//	1147
		Resolution Pitch for Integrated		
10/703,453	11/10/2003	Circuits	N/A	NA
10/7 00,400	11/10/2000			
		Method for Reducting Dimensions		
09/978,546	10/18/2001	Between Patterns on a Photoresist	N/A	NA
		Method for Eliminating Standing		
10/177,145	6/24/2002	Waves in a Photoresist Profile	N/A	NA
		Method for Detecting Solvent		
·		Leakage During Manufacture of a		
10/241,486	9/12/2002		N/A	NA
		Memory Device and Method of		
10/223,327 8/20/2002			N/A	NA
		Method of Fabricating ONO		
		Dielectric for Non-Volatile	N1/A	
10/376,225	3/3/2003		N/A	NA
40/007 400	2/4 4/0000	Method of Forming An Embedded	N/A	NA.
10/387,488	3/14/2003		N/A	NA
10/694 000	10/0/2002	Defect Reduction Using Pad	N/A	NA
10/681,099	10/9/2003	Conditioner Cleaning	IV/A	INA

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SERIAL NUMBER	FILING DATE	TITLE	PATENT NUMBER	ISSUE DATE
		Method of Preventing Over-Erase		
		of Memory Devices		
		Method for Eliminating Standing		
10/176,061	6/21/2002	Waves in a Photoresist Profile	N/A	NA
		Self-Aligned Patterning in Dual		
10/076,630	2/19/2002	Damascene Process	N/A	NA
		Method for Forming Tungsten		
		Plugs to Prevent Corrosion		
10/137,406	5/3/2002	Complexity	N/A	NA
<u> </u>		Method for Forming Self-Aligned		
10/186,892	7/2/2002	Salicides	N/A	NA
		Method for Reduced Photoresist		
10/210,032	8/2/2002	Usage	N/A	NA
		Method of Forming Self-Aligned		
10/403,060	4/1/2003	Contracts	N/A	NA
		Method for Suppressing Boron		
		Penetration by Implantation in P*		
10/656,224	9/8/2003	Mosfets	N/A	NA
		Non-Volatile Memory Cell and		
10/756,777	1/14/2004	Operating Method	N/A	NA
		Sub-90nm Space and Hole		
		Patterning Using 248nm		
		Lithography with Plasma-		
60/390,183	6/21/2002	Polymerization Coating	N/A	NA
		Method for Eliminating Polycide		
		Voids Through Nitrogen 🏅		
		Implantation	N/A	NA
		Method for Reducing Dimensions		
10/465,848	6/20/2003	Between Patterns on a Photomask	N/A	NA
		Method of Modulating Threshold		
10/417,105	4/17/2003		N/A	NA
		Method for Forming Shallow		
		Trench Isolation With Control of	:	
10/385,483	3/12/2003	Bird Beak	N/A	NA
-		Method for Plymer Removal After		
10/376,229	3/3/2003	an Etching Process	N/A	NA
		Method for Shrinking Dimensions		
10/465,850	6/20/2003	of Photoresist	N/A	NA
		Method and System for		
		Lithography Using Phase-Change		
10/315,003			N/A	NA

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